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Classification:
- **International:** H05H1/46; C01B31/06; C23C16/50; C23F4/00;
H01L21/205; H01L21/3065; H01L21/31
- **European:**
Application number: JP19980048028 19980227
Priority number(s):

PROBLEM TO BE SOLVED: To provide a plasma generating electrode that is hardly corroded even if it is exposed to plasma under a corrosive halogen gas, and can generate good quality plasma for a long time without giving adverse effect such as particles on a semiconductor wafer or the like.

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